

# Gasonics L3300

The Gasonics L3300 plasma system is designed for ashing and cleaning semiconductor wafers. Gasonics L3300 does this by creating monatomic oxygen, the active species, which chemically reacts with the photoresist on the surface of the wafer.

[Description](#)

## Description

**Model:** Gasonics L3500 Asher semiconductor process equipment

**Category:** [Plasma Asher](#)

**Original Equipment Manufacturer:** [Gasonics](#)

**Robot upgrade:** HINE Hatm 5.0 atmospheric robot arm

**Wafer Size:** 6 inch configuration.

Process Gasses: O2 and N2

estimated weight: 200kg